

Surface wave supporting structures in the terahertz and optical frequency domains

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ENGINEERING**
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Outline

- Overview
- Background
- Theory and Methods
 - Subwavelength phenomena - Dispersion relations
 - Existence of plasmonic behavior - Sommerfeld Integral analysis
 - Surface Integral equation scheme
- Applications
 - Super-resolution Imaging scheme
- Conclusions

Overview

- Plasmonics: subwavelength localization of electromagnetic (EM) fields
- Bridging the THz gap

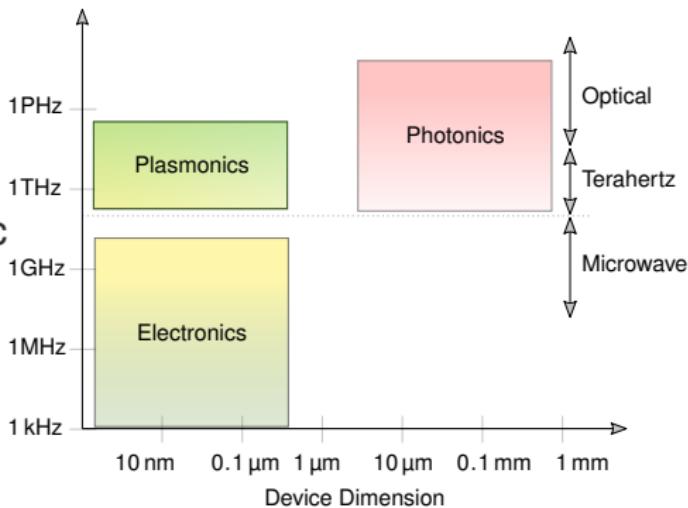


Figure: Communication Technologies at various frequencies

Overview

Terahertz 2DES

- Graphene
 - Grown separately, transferred to substrate
 - Currently not integrable to current electronics technology
 - Superior electronic properties
- Semiconductor heterostructures
 - Conventional epitaxial semiconductor device fabrication techniques
 - On-chip integration with silicon electronics

Background

Plasmonics Overview

- Interfacial wave phenomena
 - Metal-dielectric interface
 - Semiconductor heterostructure
- Surface plasmon polaritons (SPPs)
- Plasma frequency
 - Metals - Optical frequency
 - Semiconductors - Terahertz

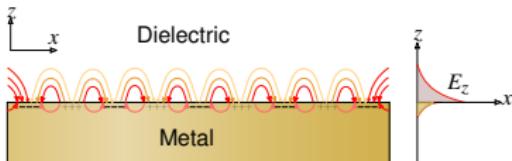


Figure: SPPs at optical frequencies

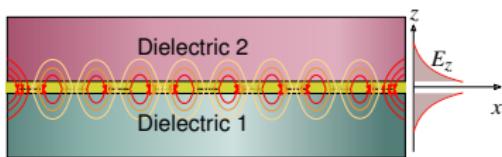


Figure: SPPs in the THz regime

Background

Surface Plasmon Polaritons

- Slow surface waves
- Reduced Wavelength
- Focusing beyond the diffraction limit
- Optical SPP

$$\text{Re} [\varepsilon_{\text{metal}}(\omega)] < 0$$

- THz SPP

$$\text{Im} [\sigma_s(\omega)] < 0$$

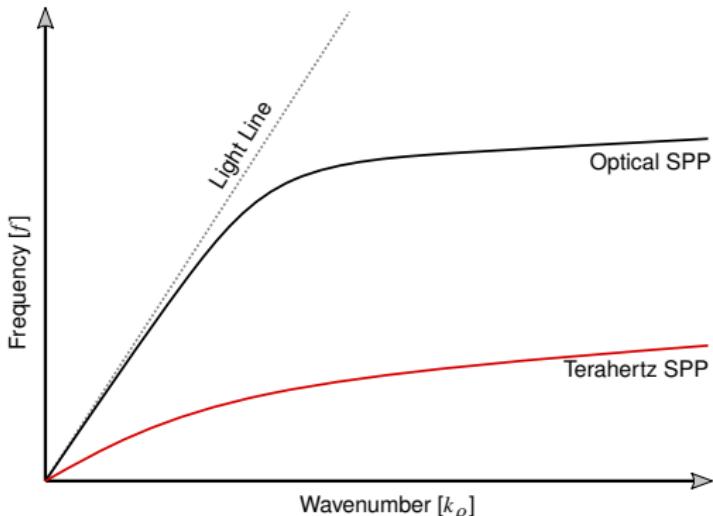


Figure: Dispersion Curve comparison

Background

Optical Nanoantennas

- Convert Localized near-field to efficient far-field radiation
- Low Q-factor
- Extremely small size
- High Purcell Factor

$$P = \frac{Q}{V}$$

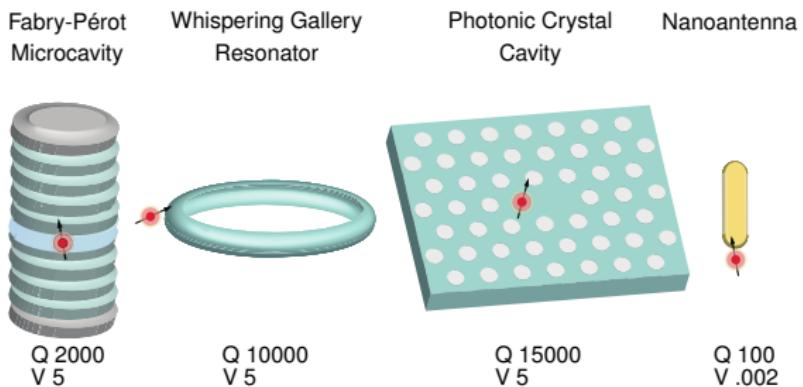


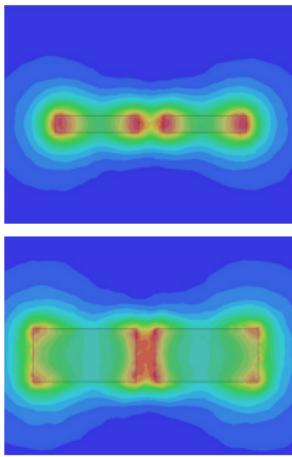
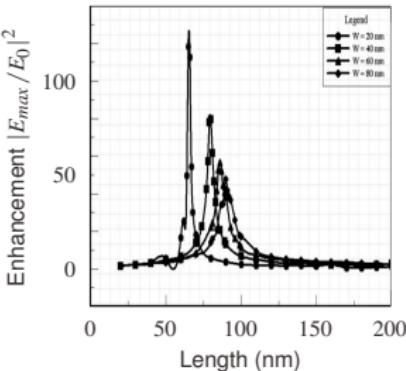
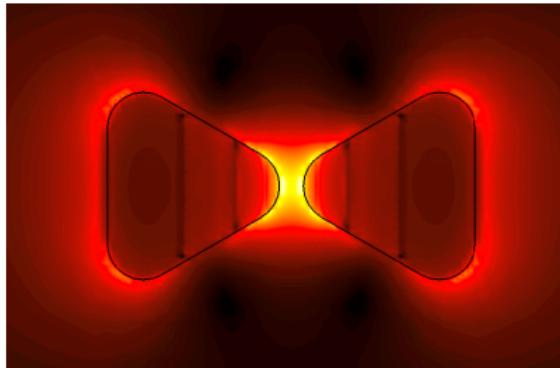
Figure: Optical resonant cavities for electric field enhancement

- Directive radiation

Background

Optical Nanoantennas (contd.)

- Scaled-down microwave antenna designs
- Shift of resonance with width unlike in microwave regime



Background

Two-dimensional Electron Gas (2DEG)

- Semiconductor Heterostructure in high electron mobility transistor (HEMT)
- High concentration of free electrons ($\sim 1 \times 10^{11} - 1 \times 10^{14} \text{ cm}^{-2}$)
- Very high Mobility ($\sim 1 \times 10^3 - 1 \times 10^6 \text{ cm}^2/\text{V}\cdot\text{s}$)
- Formation of Quantum Well
 - Two-dimensional confinement of electrons

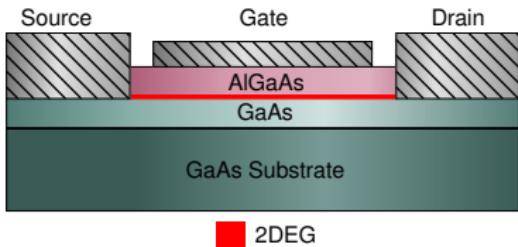


Figure: Typical GaAs/AlGaAs HEMT

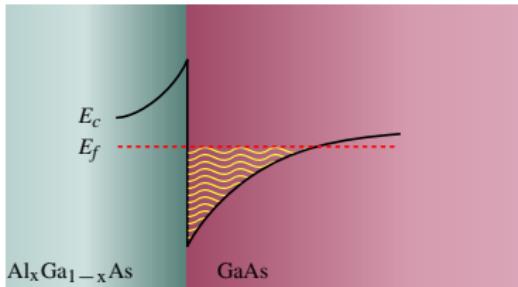
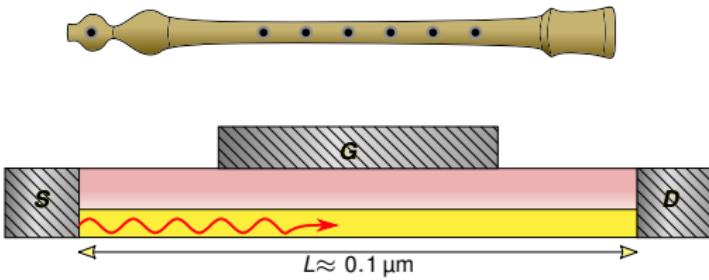


Figure: Band diagram of a GaAs/AlGaAs heterostructure

Background

2DEG (contd.)

- Plasma waves in 2DEG
- Dyakonov-Shur instability
 - Voltage bias at source and drain terminals
 - Plasma resonance
 - THz emission
- Electronic Flute
- Tunable resonance with gate voltage



$$\lambda = \frac{c}{f}$$
$$\implies 300\mu\text{m}$$

Theory

SPP Dispersion Relation

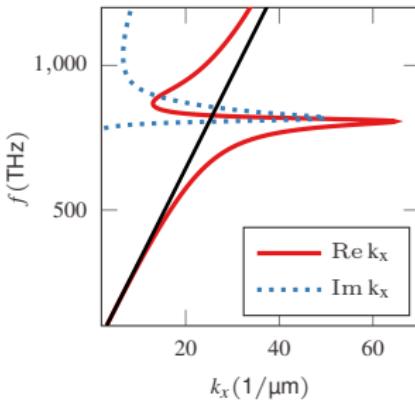
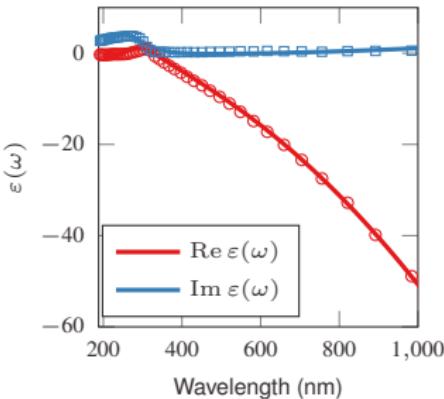
- SPP pole

$$k_{sp} = \frac{\omega}{c} \sqrt{\frac{\varepsilon_1 \varepsilon_2(\omega)}{\varepsilon_1 + \varepsilon_2(\omega)}}$$

- Accurate material description

$$\varepsilon_2(\omega) = \varepsilon_\infty - \frac{\omega_d^2}{\omega^2 - j\gamma\omega} + \sum_{i=1}^N G_i(\omega)$$

$$G_i(\omega) = C_i \left[\frac{e^{j\phi_i}}{\omega_i + \omega - j\Gamma_i} + \frac{e^{-j\phi_i}}{\omega_i - \omega + j\Gamma_i} \right]$$



Theory and Methods

2DEG Circuit model

- Drude-Lorentz Surface Conductivity

$$\sigma_s = \frac{N_s e^2}{m^*} \frac{\tau}{1 + j\tau\omega}$$

N_s - Surface charge density

τ - Scattering time

m^* - Effective electron mass

- Equivalent Circuit

$$\sigma_s = \frac{1}{Z} = \frac{1}{R + 1/j\omega C}$$

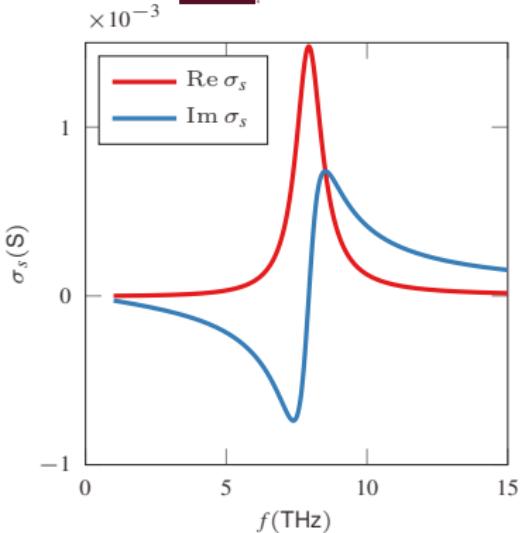


Figure: Room temperature GaN/AlGaN 2DEG surface conductivity

$$Z = R - \frac{j}{\omega C}$$



Theory and Methods

Dispersion Relation for a 2D Sheet

- Conductive Sheet in freespace
- TM mode surface wave

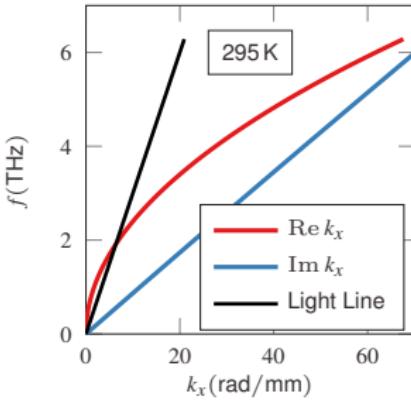
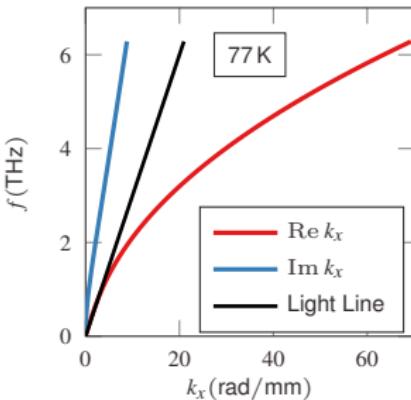
$$k_P^{\text{TM}} = \frac{\omega}{c} \sqrt{1 - \left(\frac{2}{\eta_0 \sigma_s} \right)^2}$$

- Below plasma frequency

$$\text{Im } \sigma_s < 0$$

- At low temperature

$$\text{Im } |\sigma_s| \gg \text{Re } |\sigma_s|$$



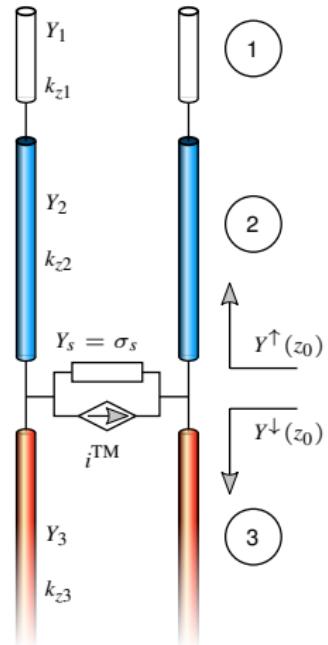
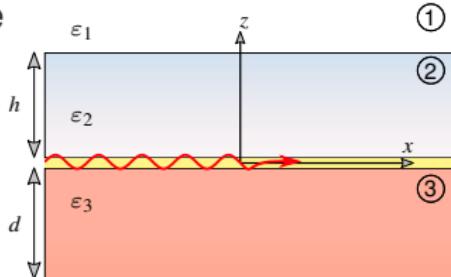
Theory and Methods

Dispersion Relation - Multilayer structures

- Equivalent transmission line (TL) network
- Dispersion relation
 - Transverse resonance condition

$$Y^{\uparrow}(z_0) + Y^{\downarrow}(z_0) + Y_{\sigma} = 0.$$

- Different configurations
 - Gated
 - Ungated
 - Backgated



Theory and Methods

Dispersion Relation - Ungated 2DEG

$$Y^\uparrow = Y_2 \frac{1 - \Gamma^\uparrow}{1 + \Gamma^\uparrow}$$

$$\Gamma^\uparrow = \frac{Y_2 - Y_1}{Y_2 + Y_1} e^{-2jk_{z2}h}$$

$$Y^\downarrow = Y_3$$

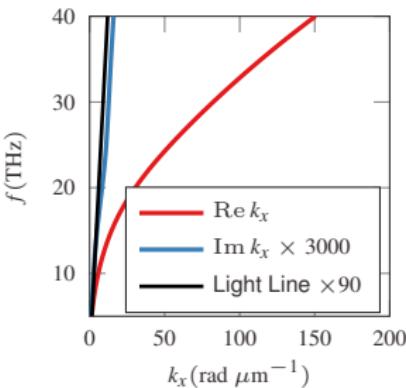
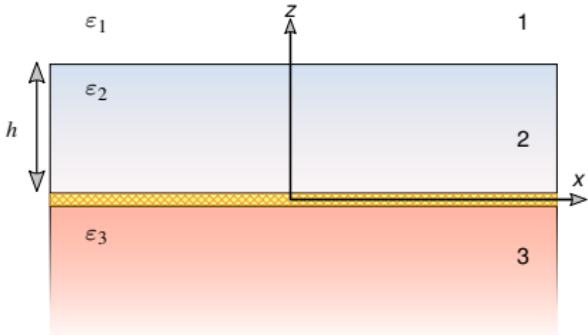
GaN/AlGaN heterostructure

N_s - $5 \times 10^{13} \text{ cm}^{-2}$

τ - $1.4 \times 10^{-10} \text{ s}$

m^* - $0.2m_e$

h - 20 nm

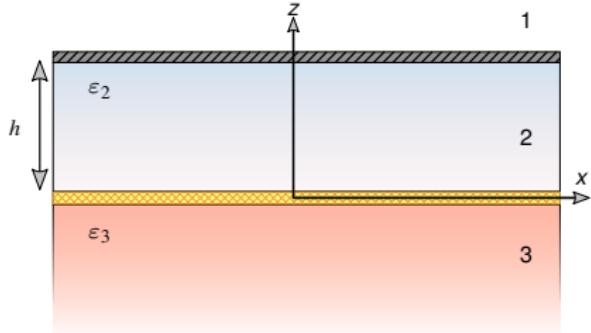


Theory and Methods

Dispersion Relation - Gated 2DEG

$$Y^\uparrow = -Y_2 \coth(k_z h)$$

$$Y^\downarrow = Y_3$$



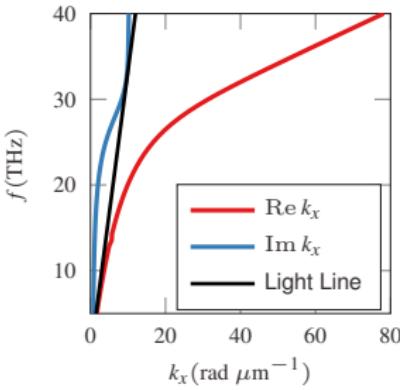
GaN/AlGaN heterostructure

$$N_s = 5 \times 10^{13} \text{ cm}^{-2}$$

$$\tau = 1.4 \times 10^{-10} \text{ s}$$

$$m^* = 0.2 m_e$$

$$h = 20 \text{ nm}$$



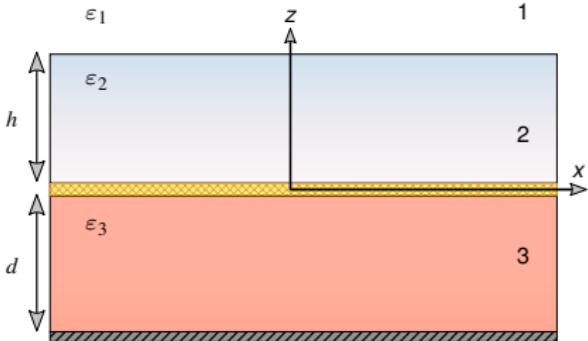
Theory and Methods

Dispersion Relation - Backgated 2DEG

$$Y^\uparrow = Y_2 \frac{1 - \Gamma^\uparrow}{1 + \Gamma^\uparrow}$$

$$\Gamma^\uparrow = \frac{Y_2 - Y_1}{Y_2 + Y_1} e^{-2jk_{z2}h}$$

$$Y^\downarrow = -Y_3 \coth(k_{z3}d)$$



GaN/AlGaN heterostructure

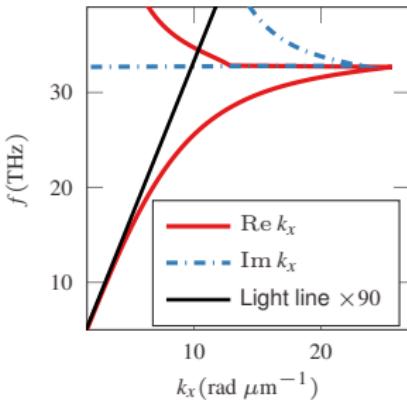
N_s - $5 \times 10^{13} \text{ cm}^{-2}$

τ - $1.4 \times 10^{-10} \text{ s}$

m^* - $0.2m_e$

h - 20 nm

d - 50 nm



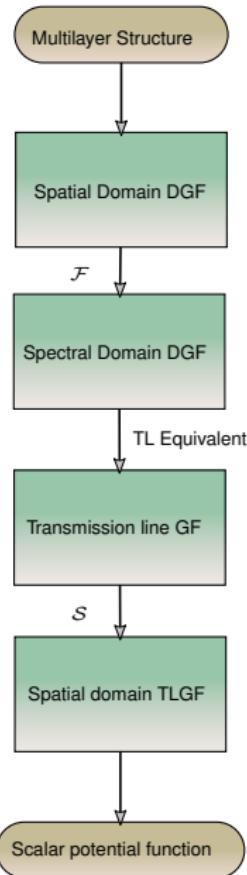
Theory and Methods

Field Computation of layered media

- Methods using discretization computationally expensive
 - Finite element method (FEM)
 - Finite Difference Time Domain (FDTD)
- Integral equation (IE) approach most suitable
 - Formulation of dyadic Green function (DGF)

$$\mathbf{E} = \int_{r'} \underline{\underline{\mathbf{G}}}^{\text{EJ}}(\mathbf{r}|\mathbf{r}') \mathbf{J}(\mathbf{r}') \, d\mathbf{r}',$$

$$\mathbf{H} = \int_{r'} \underline{\underline{\mathbf{G}}}^{\text{HJ}}(\mathbf{r}|\mathbf{r}') \mathbf{J}(\mathbf{r}') \, d\mathbf{r}'.$$



Theory and Methods

Field Computation - Thin sheet

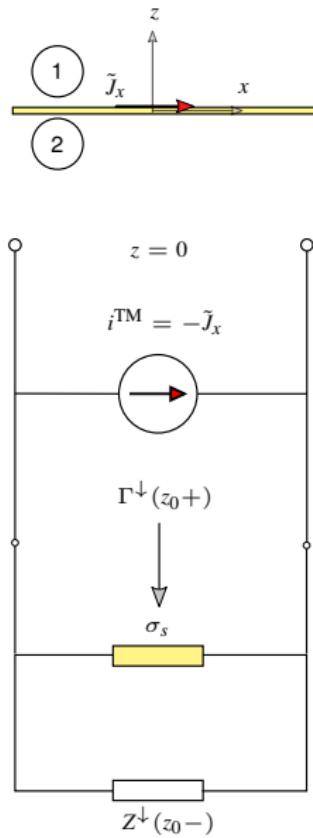
- Thin conductive sheet in free-space

$$Z^\downarrow(z_0^+) = \frac{Z_0}{1 + \sigma_s Z_0}$$

$$\Gamma^{\downarrow, \text{TE}} = \frac{k_{z1} - \omega\mu_1\sigma_s}{k_{z1} + \omega\mu_1\sigma_s}$$

$$\Gamma^{\downarrow, \text{TM}} = \frac{\omega\varepsilon_1 - \sigma_s k_{z1}}{\omega\varepsilon_1 + \sigma_s k_{z1}}$$

$$G_{zx}^A = \frac{j\mu}{2} \cos \phi \mathcal{S}_1 \left\{ \frac{\Gamma^{\downarrow, \text{TM}} - \Gamma^{\downarrow, \text{TE}}}{k_\rho} \right\}.$$



Theory and Methods

Computed Fields - Thin sheet

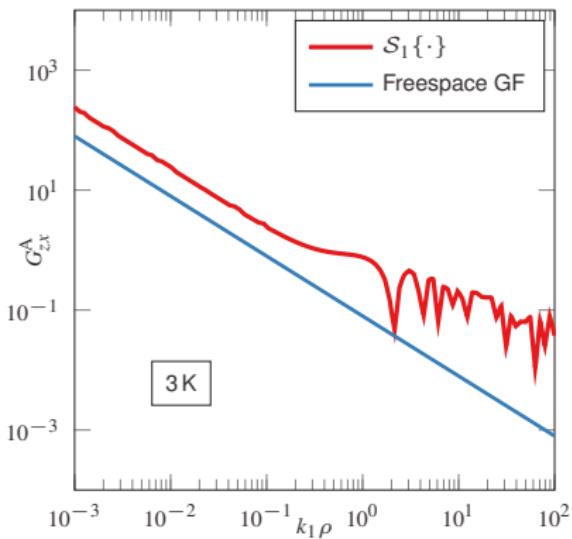
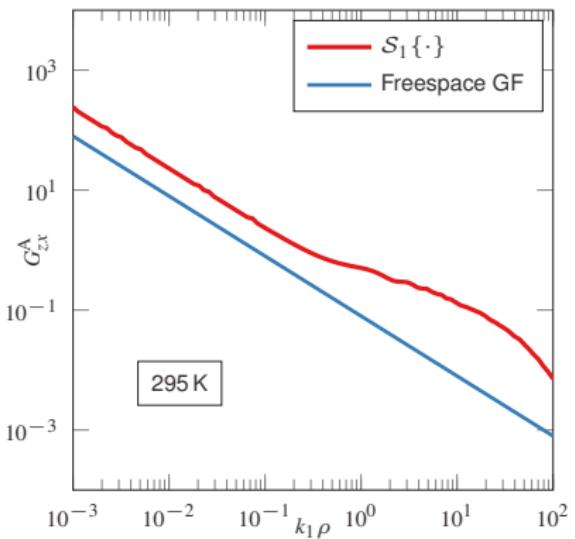


Figure: G_{zx}^A computed for a GaN/AlGaN based 2DEG sheet suspended in freespace at 5.6 THz. The surface conductivity of the sheet is (a) $\sigma_s = 7.6 \times 10^{-5} - j2.98 \times 10^{-3}$ S at room temperature (300 K), and (b) $\sigma_s = 7.6 \times 10^{-8} - j2.98 \times 10^{-3}$ S at 3 K

Theory and Methods

Thin Sheet Simulation

- Volume Integral formulation

$$\mathbf{A} = \frac{\mu}{4\pi} \int_V \mathbf{J}_v(\mathbf{r}') \frac{e^{-jk_1|\mathbf{r}-\mathbf{r}'|}}{|\mathbf{r}-\mathbf{r}'|} dv'$$

$$\mathbf{E}_1^{scat} = -\frac{j\omega}{k_1^2} (k_1^2 + \nabla \nabla \cdot) \mathbf{A}$$

$$\mathbf{J}_v = \frac{-jk_1}{Z_0} (\epsilon_2 - 1) \mathbf{E}_2$$

- Impedance (Leontovich)
Boundary Condition

$$\mathbf{E}_{tan} = \eta Z_0 \hat{\mathbf{n}} \times \mathbf{H}$$

$$\begin{aligned} E^i &= \eta Z_0 J_s(x') \\ &+ \frac{\omega \mu}{4} \int_l J_s(x') H_0^{(2)}(k_2 |x - x'|) dx' \end{aligned}$$

- Surface current J_s
approximated from J_v

Theory and Methods

Proposed Surface Integral Equation (SIE) scheme

- Surface Equivalence Theorem

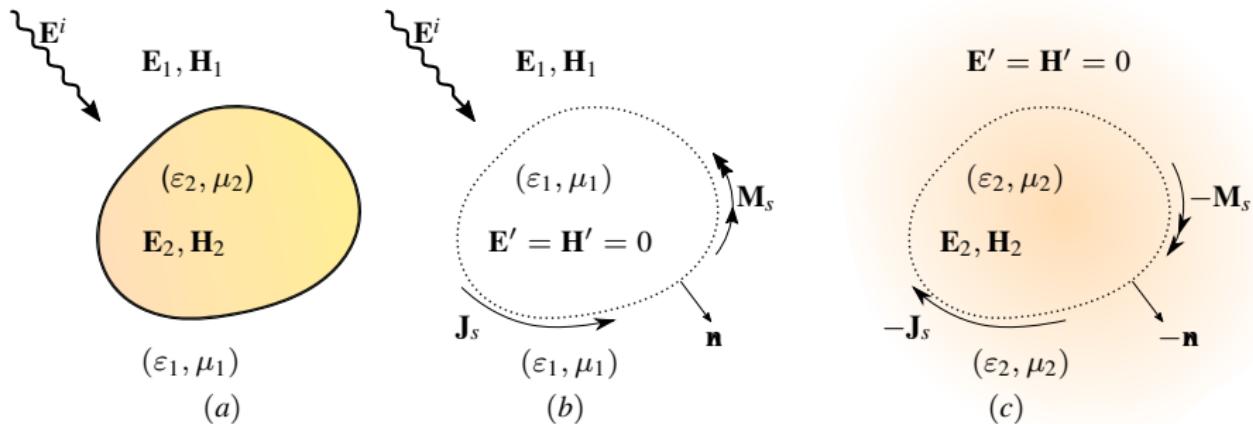


Figure: (a). Actual and its equivalent models for the (b) external and, (c) Internal region

Theory and Methods

TM_z SIE for Thin Flat Sheet

$$\hat{\mathbf{n}} \times (\mathbf{E}_1 - \mathbf{E}_2) = \mathbf{0}$$

$$E_i = \frac{\omega}{4} \int_L J_z(x') \left[H_0^{(2)}(k_1|x-x'|) + H_0^{(2)}(k_2|x-x'|) \right] dx'$$

$$\hat{\mathbf{n}} \times (\mathbf{H}_1 - \mathbf{H}_2) = \mathbf{0}$$

$$H_i^{tan} = \frac{-j\omega}{2} \int_L M_x(x') \left[\varepsilon_1 H_0^{(2)}(k_1|x-x'|) + \varepsilon_1 H_2^{(2)}(k_1|x-x'|) \right. \\ \left. + \varepsilon_2 H_0^{(2)}(k_2|x-x'|) + \varepsilon_2 H_2^{(2)}(k_2|x-x'|) \right] dx'$$

Theory and Methods

Method of moments

- Integral equations to system of linear equations

$$\begin{bmatrix} Z_{mn} & 0 \\ 0 & Y_{mn} \end{bmatrix} \begin{bmatrix} J_n \\ M_n \end{bmatrix} = \begin{bmatrix} E_m^i \\ H_m^i \end{bmatrix}$$

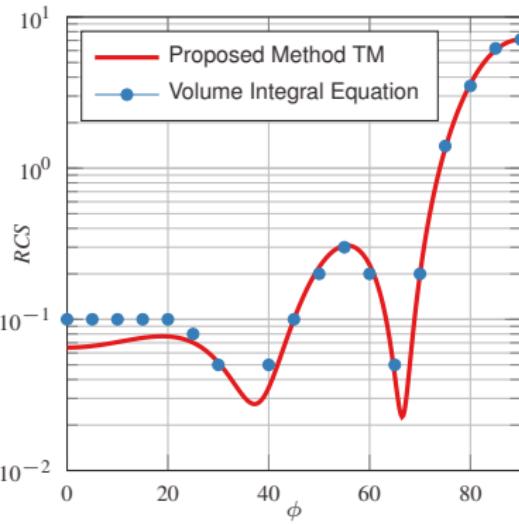
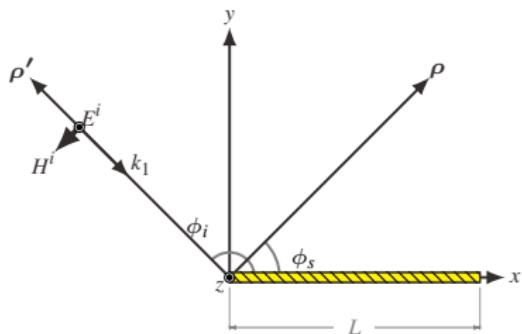
- Pulse basis functions and Point matching used
- Far-field

$$RCS(\phi) \simeq \int_0^L [J_z(x')\eta_1 + M_x(x') \sin(\phi_i)] e^{jk_1 x' \cos(\phi_i)} dx'$$

Results

Thin Sheet Simulation (TM_z)

- TM_z polarization
- Dielectric Rod of length 2.5λ
- $\epsilon = 4, \mu = 1$

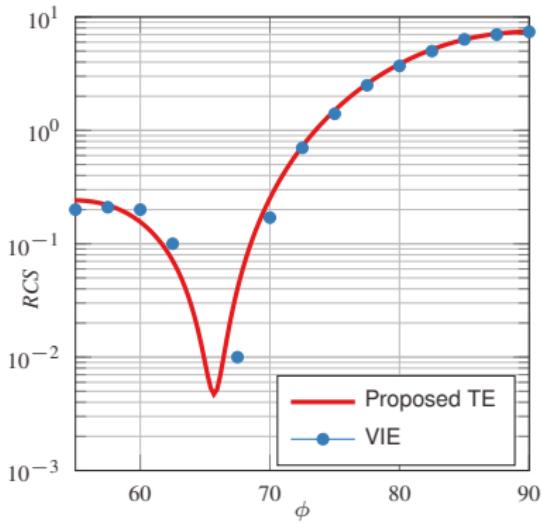
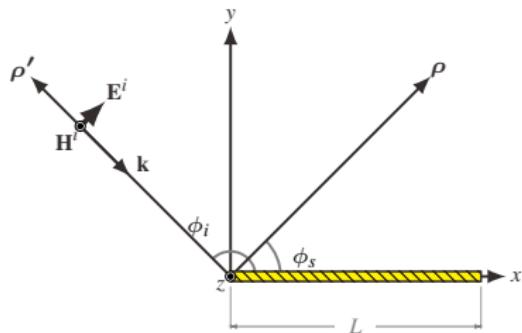


- Thickness of $.05\lambda$ assumed in Volume Integral equation model

Results

Thin Sheet Simulation (TE_z)

- TE_z polarization
- Dielectric Rod of length 2.5λ
- $\varepsilon = 4, \mu = 1$

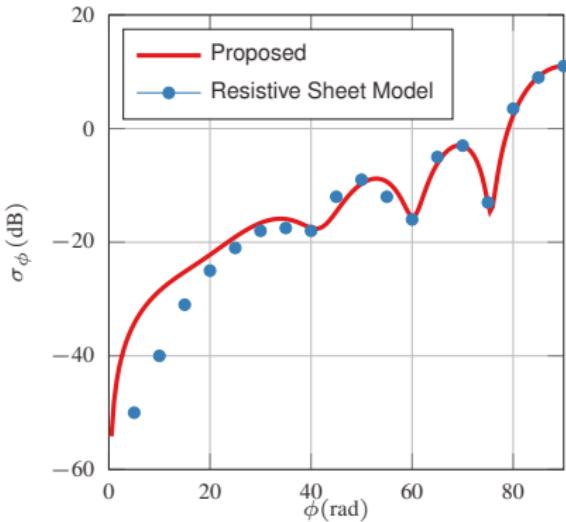
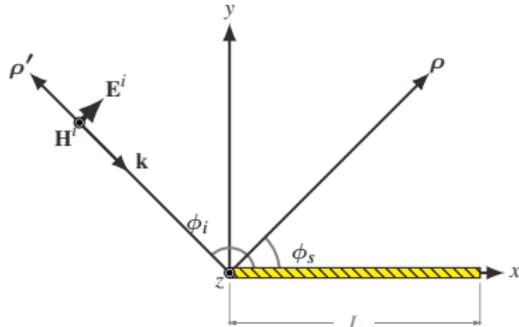


- Thickness of $.05\lambda$ assumed in Volume Integral equation model

Results

Thin Sheet Simulation (TE_z)

- TE_z polarization
- Dielectric Rod of length 2λ
- $\varepsilon = 4$, $\mu = 1$



- Thickness of $.628/k_1$ assumed in resistive model

Nanoscale Imaging

Basic Concept

- Conventional microscopy

- Uniform illumination

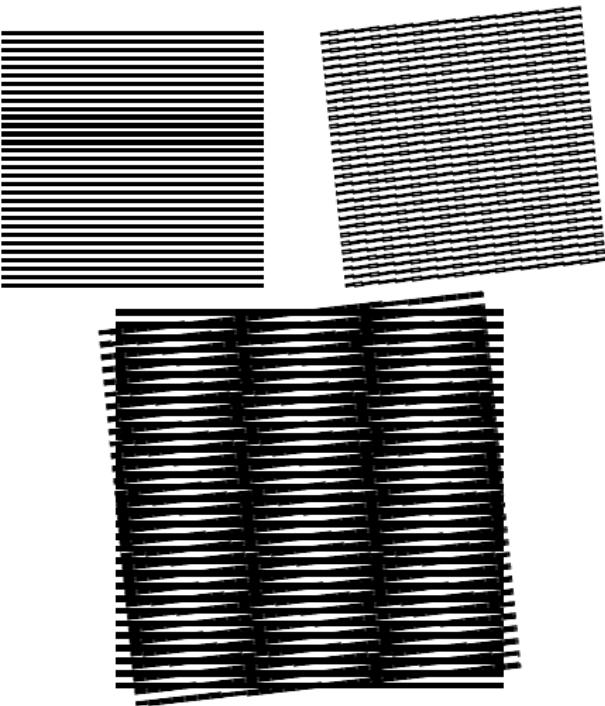
$$\text{Resolution} \approx \frac{\lambda}{2}$$

- Structured Illumination

- Periodic sine pattern

- Moiré Fringes

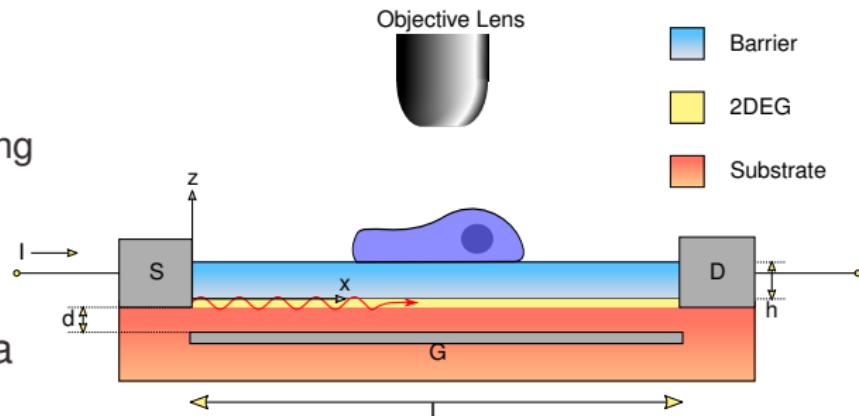
- Frequency modulation of two fine patterns results in a coarse pattern



Nanoscale Imaging

Imaging Setup

- Backgated high electron mobility transistor (HEMT)
 - Plasmonic standing wave
 - Subwavelength profile
- Tunable response via gate voltage control
- Low light intensity
- Performance limited by presence of barrier layer



Nanoscale Imaging

Working Principle

- Illumination signal

$$I(\mathbf{r}) = 1 + \cos(\mathbf{k}_\rho \cdot \mathbf{r} + \phi)$$

- Observed Image under ideal circumstances (Spatial domain)

$$M(\mathbf{r}) = [F(\mathbf{r}) \cdot I(\mathbf{r})]$$

- Fourier transformed Image

$$\begin{aligned}\tilde{M}(\mathbf{k}) &= \tilde{F}(\mathbf{k}) \otimes \tilde{I}(\mathbf{k}) \\ &= \frac{1}{2} \left[2\tilde{F}(\mathbf{k}) + \tilde{F}(\mathbf{k} - \mathbf{k}_\rho) e^{-j\phi} + \tilde{F}(\mathbf{k} + \mathbf{k}_\rho) e^{j\phi} \right]\end{aligned}$$

Nanoscale Imaging

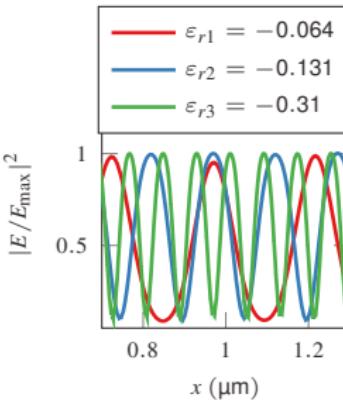
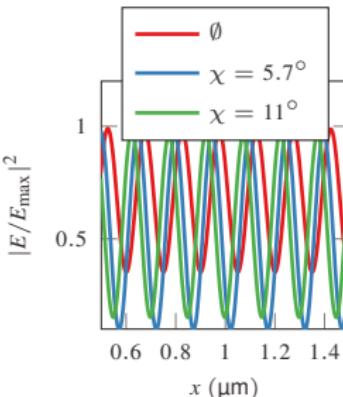
Image Reconstruction

- Three shifted versions of the sample in the observed image
- Phased shifts achieved through external TM-polarized plane wave

$$\mathbf{E}_{ext} = \hat{\mathbf{x}} a + \hat{\mathbf{z}} b$$

$$\begin{aligned}|E|^2 &= (a + \cos k_\rho x)^2 + (b + \sin k_\rho x)^2 \\&= a^2 + b^2 + 1 + 2\chi \cos(k_\rho x + \psi)\end{aligned}$$

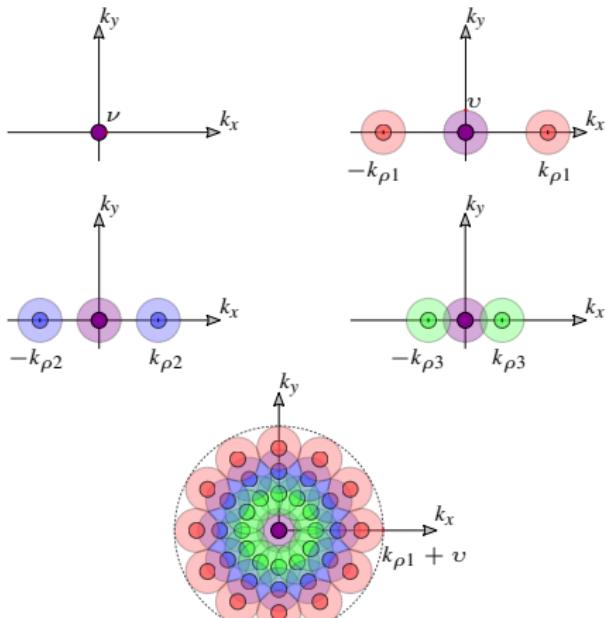
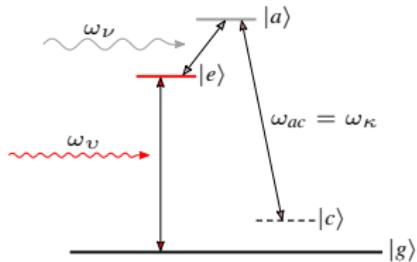
- Change in 2DEG plasma frequency by gate voltage



Nanoscale Imaging

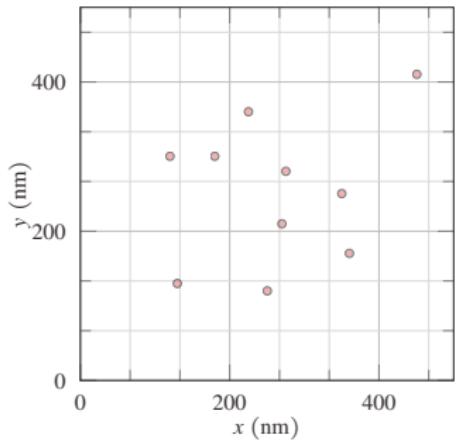
Frequency domain illustration of the scheme

- Slow imaging process
 - Many plasmonic resonances required
- Process expedited by an additional illumination

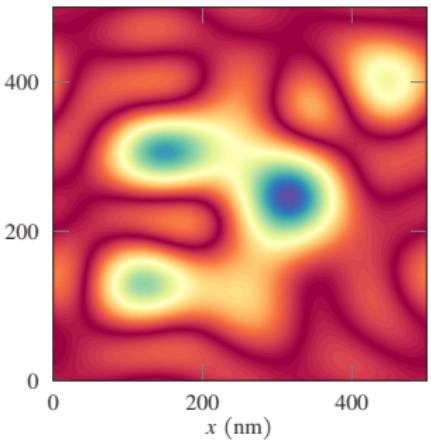


Nanoscale Imaging

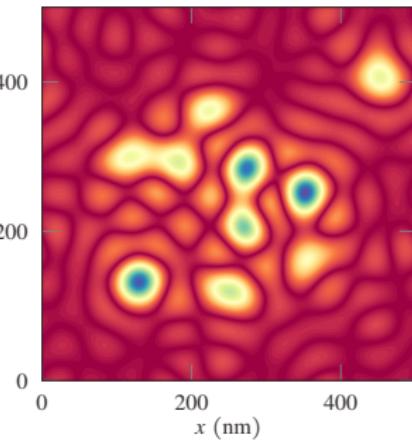
Simulation Results



(a)



(b)



(c)

Figure: (a) Sample distribution. Simulation of the reconstructed sample image at: (b)
 $\text{Re } k_\rho = 39.5$ (c) $\text{Re } k_\rho = 80$

Summary

Two-dimensional plasmonic devices

- Subwavelength wave phenomena at optical and terahertz frequencies
- Realization of terahertz sources and sensors
- 2D nature of waves permits subwavelength confinement
- Plasmonic activity
- Nanoscale imaging using terahertz plasma waves

Acknowledgements

Sponsorship

- The Fulbright Program



Thank you!

Questions?